



SHEET 1 OF 1

# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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**Tohru YAMAOKA, et al.**

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## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
/HL/		US 4,142,073	02-27-1979	AGNEUS et al.	_____
/HL/		US 2902/0181725 A1	12-05-2002	JOHANSEN et al.	_____
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## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Code - Number - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No
/HL/		JP 2002-209298	07-26-2002	SEIKO EPSON CORP.	_____	JAPAN (w/ English Abstract)
/HL/		JP 09-283373	10-31-1997	MATSUSHITA ELECTRIC WORKS LTD.	_____	JAPAN (w/ English Abstract)

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	
/HL/		European Search Report issued in European Patent Application No. EP 04818870.0-1235/1686599 PCT/JP2004/016835, dated March 13, 2009.	
/HL/		United States Office Action issued in United States Patent Application No. 10/591,456, dated January 29, 2009.	
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/HL/		T. Majama et al., "Effect of Oxidation Temperature of the Electrical Characteristics of Ultrathin Silicon Dioxide Layers Plasma Oxidized in Ultrahigh Vacuum," Physica Scripta, Vol. T79, pp. 259-262, 1999.	
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/Huyen Le/ EXAMINER		DATE CONSIDERED 11/17/2009	

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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